

ECE 6745 Complex Digital ASIC Design

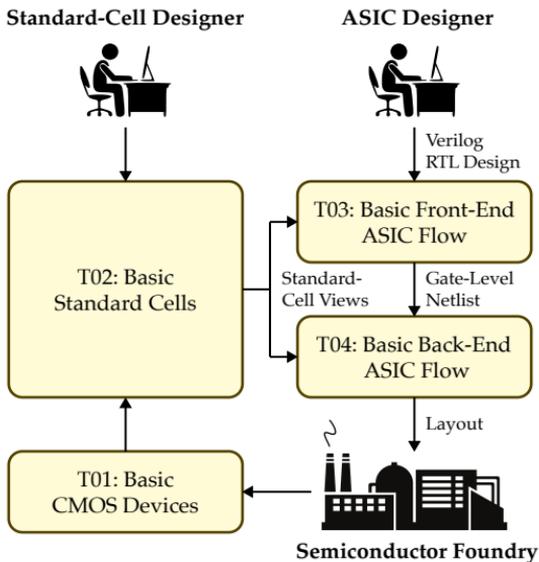
Topic 2: Basic Standard Cells

School of Electrical and Computer Engineering
Cornell University

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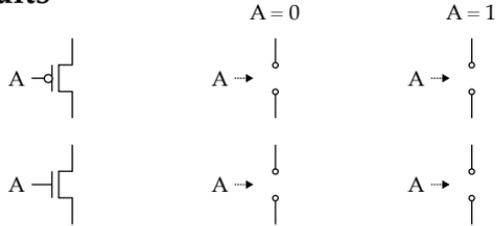
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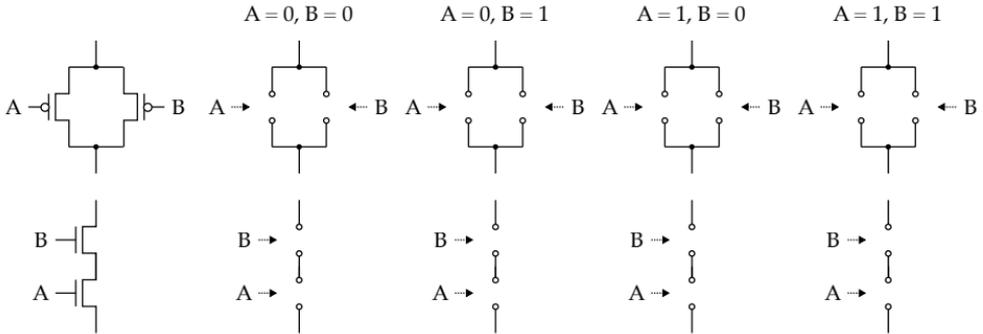
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1. Static CMOS Circuits

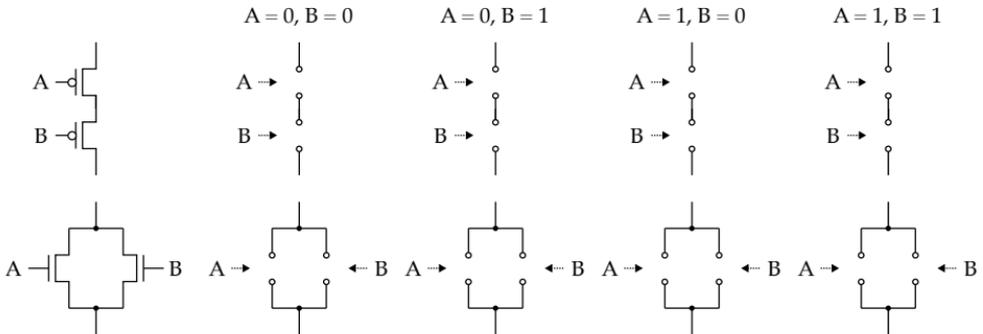
- A PMOS transistor is the **complement** of an NMOS transistor



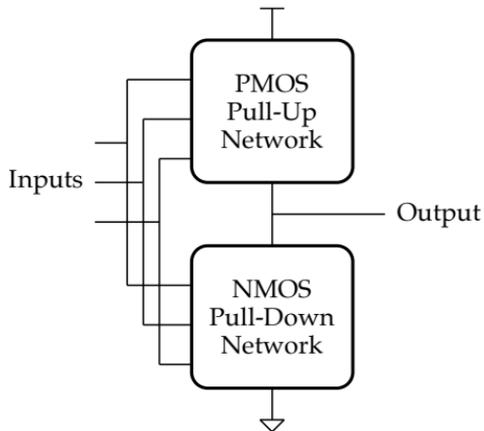
- PMOS in parallel are the **complement** of NMOS in series



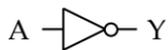
- PMOS in series are the **complement** of NMOS in parallel



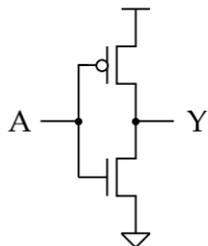
- **Static CMOS circuits** are divided into two parts:
 - Pull-up network exclusively uses PMOS transistors
 - Pull-down network exclusively uses NMOS transistors
- Pull-up network is the **complement** of the pull-down network
 - Every input is connected to exactly one PMOS and one NMOS
 - If one network is ON, the other network is OFF
 - Both networks are never ON at the same time (i.e., there is never a direct current path from VDD to ground)
 - Both networks are never OFF at the same time (i.e., the output should never be floating)



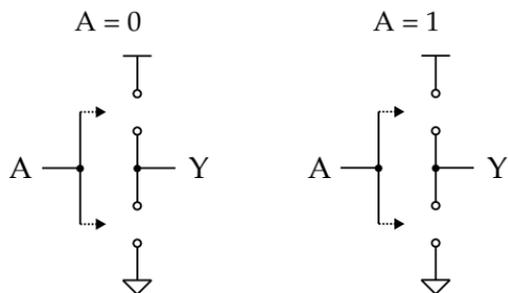
1.1. Inverter Circuit



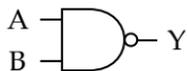
| A | Y |
|---|---|
| 0 | 1 |
| 1 | 0 |



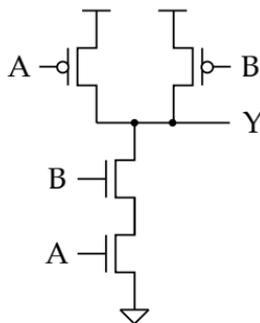
Switch-Level Model



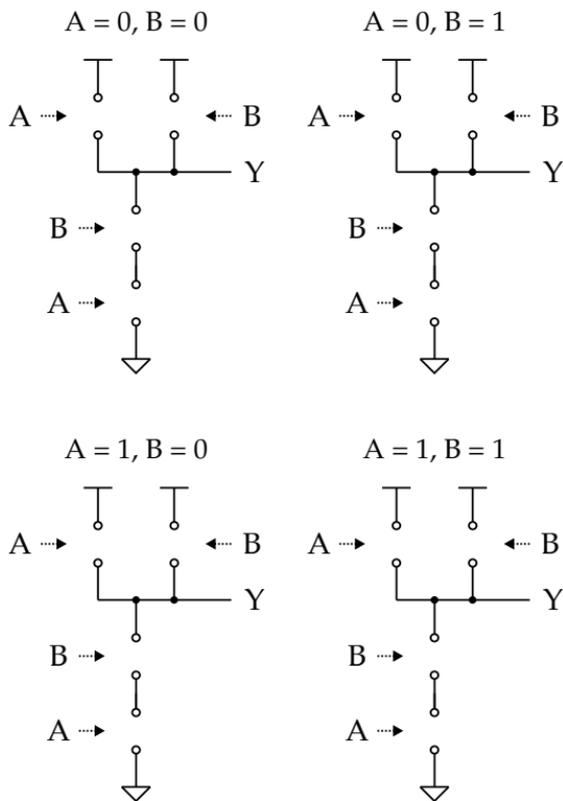
1.2. NAND2 Circuit



| A | B | Y |
|---|---|---|
| 0 | 0 | 1 |
| 0 | 1 | 1 |
| 1 | 0 | 1 |
| 1 | 1 | 0 |



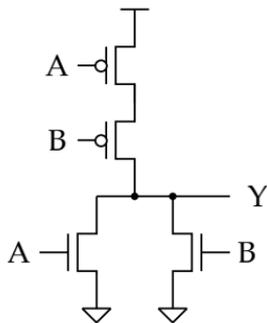
Switch-Level Model



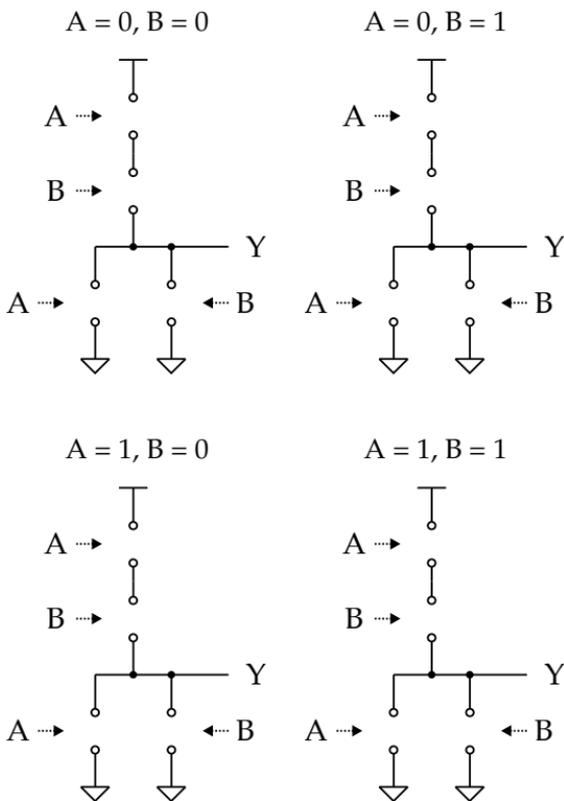
1.3. NOR2 Circuit



| A | B | Y |
|---|---|---|
| 0 | 0 | 1 |
| 0 | 1 | 0 |
| 1 | 0 | 0 |
| 1 | 1 | 0 |



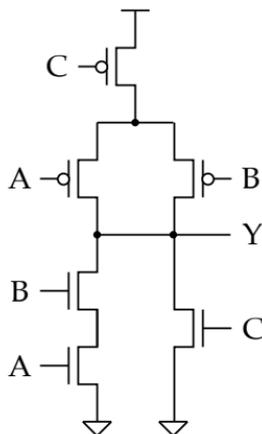
Switch-Level Model



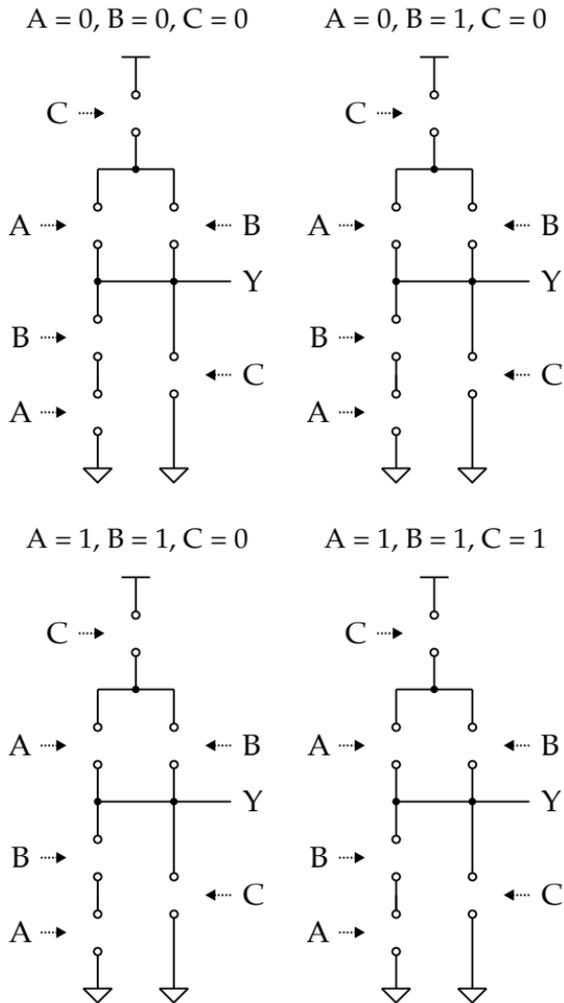
1.4. AOI21 Circuit



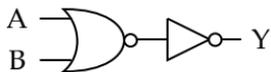
| A | B | C | Y |
|---|---|---|---|
| 0 | 0 | 0 | 1 |
| 0 | 0 | 1 | 0 |
| 0 | 1 | 0 | 1 |
| 0 | 1 | 1 | 0 |
| 1 | 0 | 0 | 1 |
| 1 | 0 | 1 | 0 |
| 1 | 1 | 0 | 0 |
| 1 | 1 | 1 | 0 |



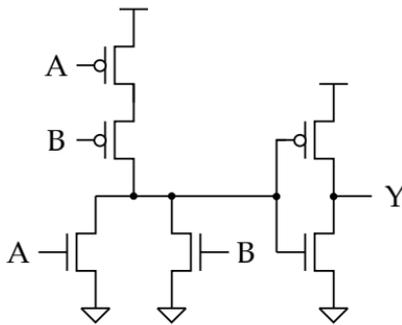
Switch-Level Model



1.5. Multi-Stage Circuits

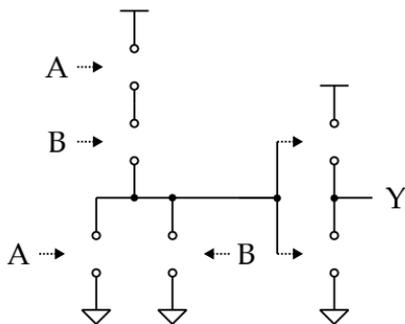


| A | B | Y |
|---|---|---|
| 0 | 0 | 0 |
| 0 | 1 | 1 |
| 1 | 0 | 1 |
| 1 | 1 | 1 |

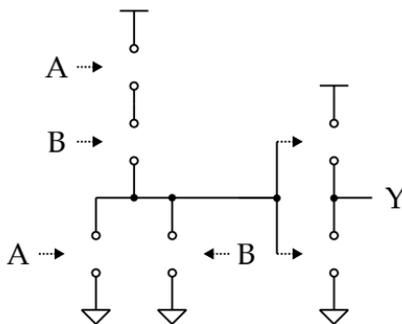


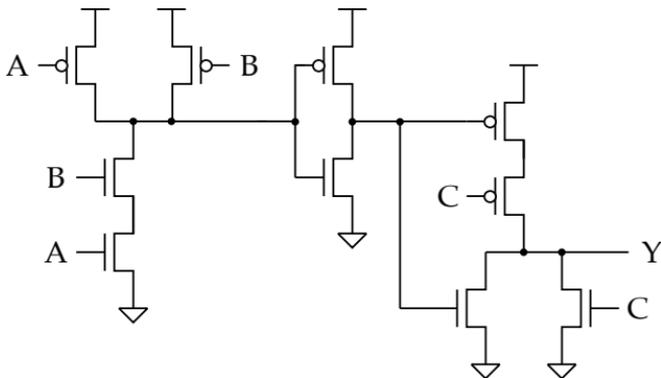
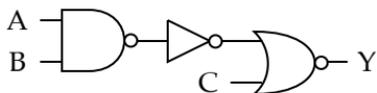
Switch-Level Model

A = 0, B = 0



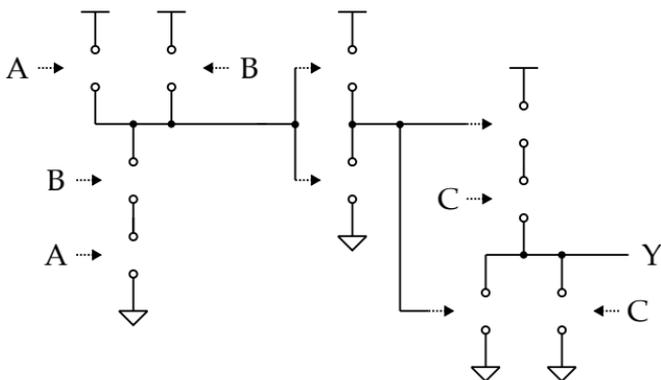
A = 0, B = 1



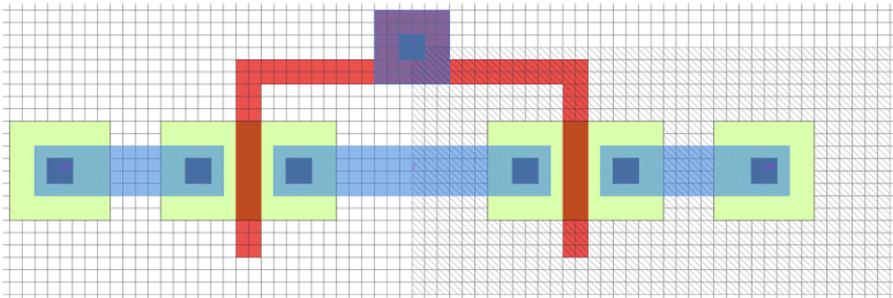


Switch-Level Model

$A = 1, B = 1, C = 0$

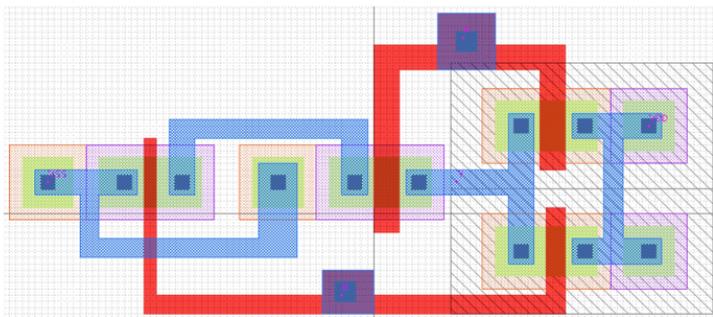


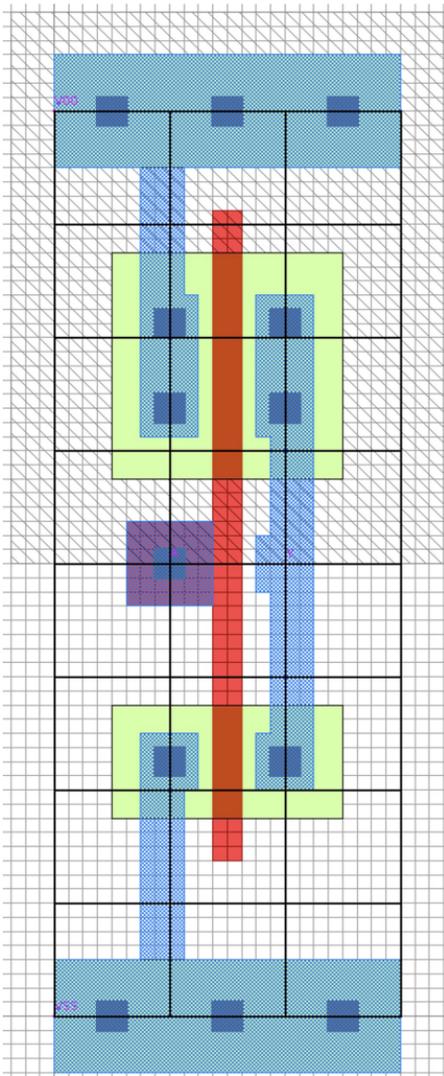
2. Full-Custom vs. Standard Cell Design



2.1. Full-Custom Design

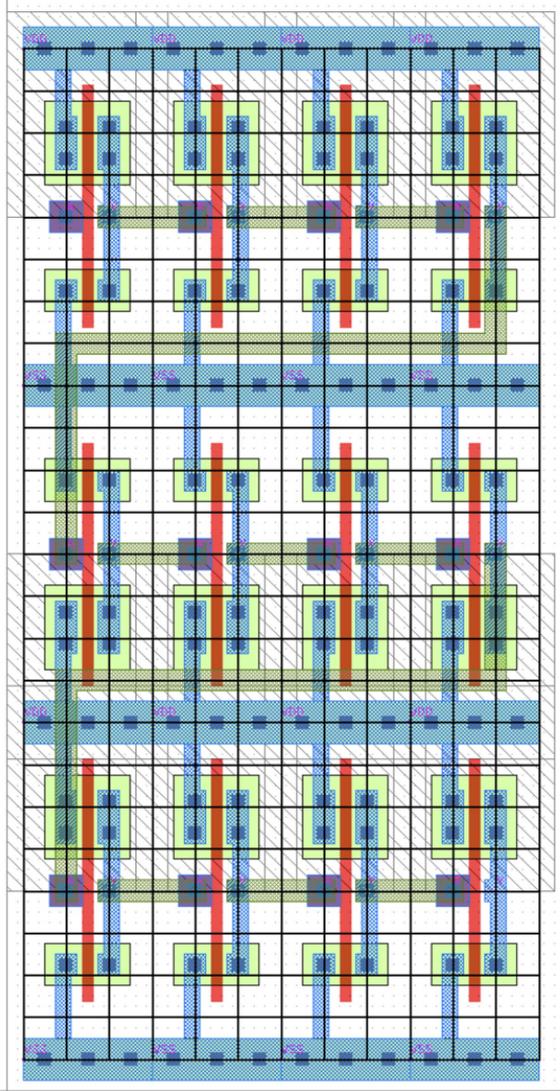
- Transistors can be in any position and any orientation
- N-well can be any size and in any location
- VDD and ground can use any metal layer and any location
- Substrate and n-well contacts can be in any location
- Metal routing is unconstrained
- Cells can be any height and any width
- Pins can be on any layer and in any location
- Cells can have any drive strengths with non-equal rise and fall times





2.2. Standard-Cell Design

- **Standard** transistor positions and orientation (PMOS at top, NMOS at bottom, vertical gates)
- **Standard** n-well size and location (n-well at top)
- **Standard** VDD and ground metal layer and locations (on metal 1, VDD rail 8λ tall at top, ground rail 8λ tall at bottom)
- **Standard** n-well and substrate contacts
- **Standard** boundary and extension of n-well, VDD, and ground rails beyond boundary (origin is in lower left)
- **Standard** metal 2+ routing grid (8λ track spacing)
- **Standard** cell height (64λ)
- **Standard** cell width (aligned to routing grid, i.e., 8λ , 16λ , 24λ , etc)
- **Standard** routing (all routing must be on polysilicon or metal 1)
- **Standard** pin layer and locations (on metal 1 and on routing grid)
- **Standard** set of available drive strengths



- Standard cells are designed to be abutted in rows
 - n-wells align
 - VDD rails align
 - Ground rails align
 - N-well contacts align
 - Substrate contacts align
- Each row is flipped vertically with respect to previous row
 - Enables sharing VDD and ground rails
- Standard-cell design rules ensure composing standard cells will not create any DRC violations
- Metal 2+ always routed on the routing grid

2.3. Standard-Cell Views

| | |
|--------------------------|---|
| Behavioral View | Logical function of the standard cell, used for gate-level simulation |
| Schematic View | Transistor-level representation of standard cell, used for functional verification and layout-vs-schematic (LVS) |
| Layout View | Layout of standard cell, used for design-rule checking (DRC), layout-vs-schematic (LVS), resistance/capacitance extraction (RCX), and fabrication |
| Extracted Schematic View | Transistor-level representation with extracted resistance and capacitances, used for layout-vs-schematic (LVS) and timing characterization |
| Front-End View | High-level information about standard cell including area, input capacitance, logical function, and delay model; used in synthesis |
| Back-End View | Low-level information about standard cell including height, width, and pin locations; used in placement and routing |

3. Standard Cells

- We will initially focus on the following seven basic standard cells
 - INVX1 : NOT gate (inverter)
 - NAND2X1 : 2-input NAND gate
 - NOR2X1 : 2-input NOR gate
 - AOI21X1 : 3-input AND-OR-Inverting gate
 - TIEHI : Tie output to logic one
 - TIELO : Tie output to logic zero
 - FILL : Filler cell
- X1 suffix means these standard cells all have the same **drive strength** (i.e., approximately the same effective resistance)
- We will later discuss more advanced standard cells
 - More complex combinational logic cells
 - Sequential logic cells (i.e., flip-flops)
 - Cells with larger drive strengths

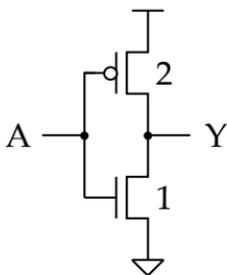
3.1. INVX1

Behavioral View

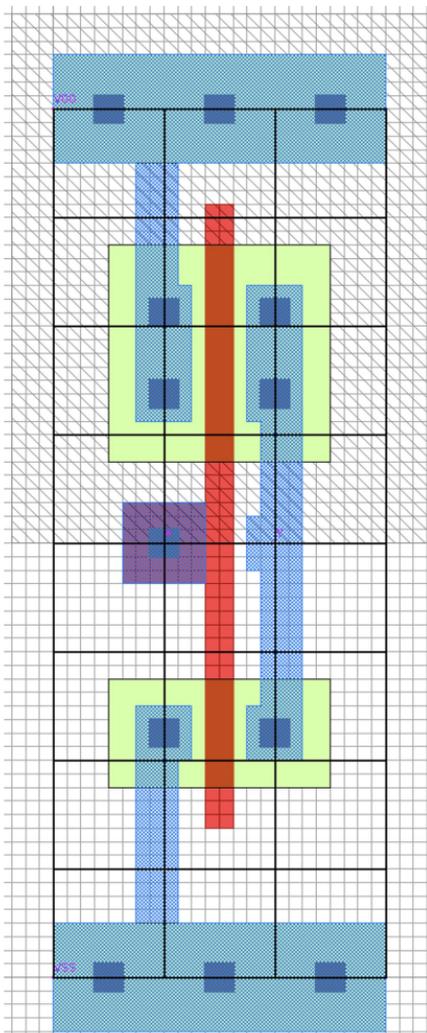
| A | Y |
|---|---|
| 0 | 1 |
| 1 | 0 |

$$Y = \bar{A}$$

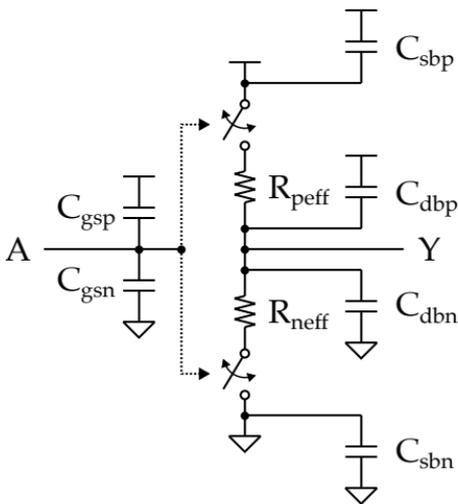
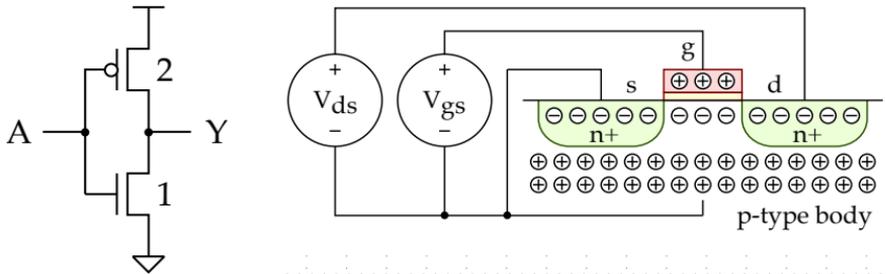
Schematic View



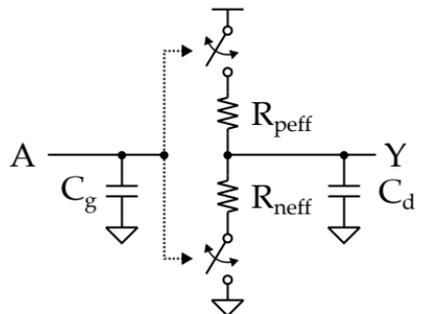
Layout View



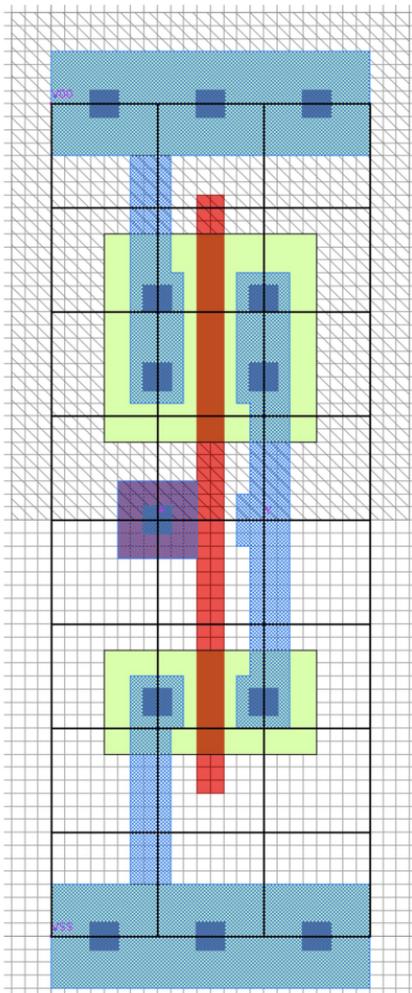
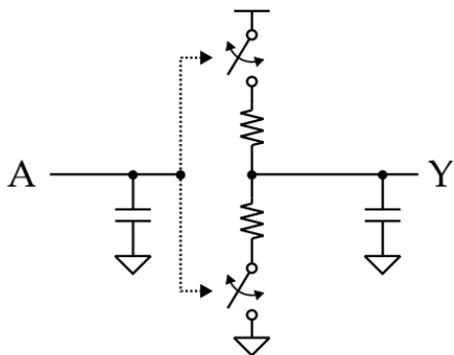
Extracted Schematic View

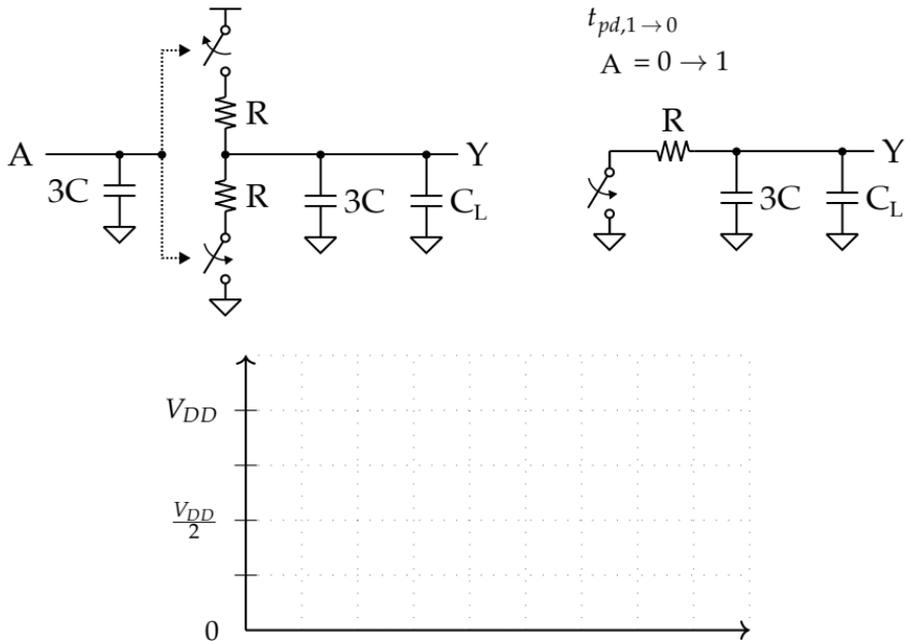


- C_{sb} capacitors do not actually switch, so ignore
- C_d and C_g capacitors tied to constant voltage sources so lump together



- C_g is the **gate capacitance**
- C_d is the **diffusion capacitance** or **parasitic capacitance**
- Let's use normalized units
 - Let R be the effective resistance of a minimum-sized NMOS
 - Let C be the gate capacitance of a minimum-sized NMOS
 - Let C be the diffusion capacitance of a minimum-sized NMOS
- Recall $R_{peff} = 2 \times R_{neff}$ for same transistor width





- Let t_{pd} be the time until $V_Y = V_{DD}/2$ (propagation delay)
- Let $\tau = R(3C + C_L) = 3RC + RC_L$ (time constant)

$$V_Y = V_{DD} e^{-t/\tau}$$

$$V_{DD}/2 = V_{DD} e^{-t/\tau}$$

$$1/2 = e^{-t/\tau}$$

$$\ln(1/2) = -t/\tau$$

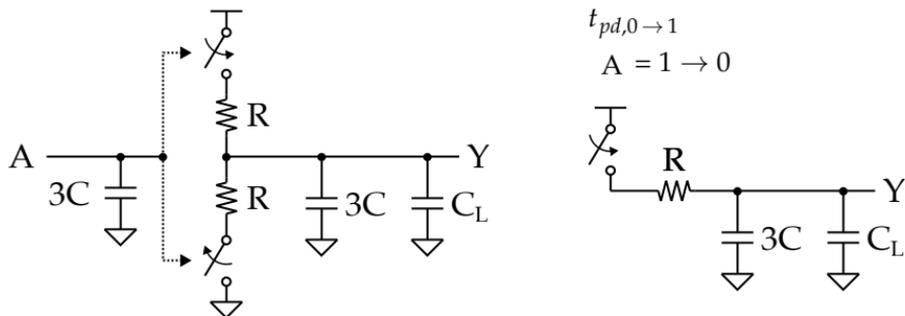
$$-\tau \ln(1/2) = t$$

$$t = \tau \ln(2)$$

- $t_{pd,1 \rightarrow 0} = (3RC + RC_L) \cdot \ln(2)$

- We usually just assume effective resistance is scaled by $\ln(2)$

$$t_{pd,1 \rightarrow 0} = 3RC + RC_L$$



- Let t_{pd} be the time until $V_Y = V_{DD}/2$ (propagation delay)
- Let $\tau = R(3C + C_L) = 3RC + RC_L$ (time constant)

$$V_Y = V_{DD} \cdot (1 - e^{-t/\tau})$$

$$V_{DD}/2 = V_{DD} \cdot (1 - e^{-t/\tau})$$

$$V_{DD}/2 = 1 - e^{-t/\tau}$$

$$\ln(1/2) = -t/\tau$$

$$-\tau \ln(1/2) = t$$

$$t = \tau \ln(2)$$

- $t_{pd,0 \rightarrow 1} = (3RC + RC_L) \cdot \ln(2)$

- We usually just assume effective resistance is scaled by $\ln(2)$

$$t_{pd,0 \rightarrow 1} = 3RC + RC_L$$

Front-End View

Cell Area

A Input Cap

Y Logic Function

Y Propagation Delay

Back-End View

Cell Height

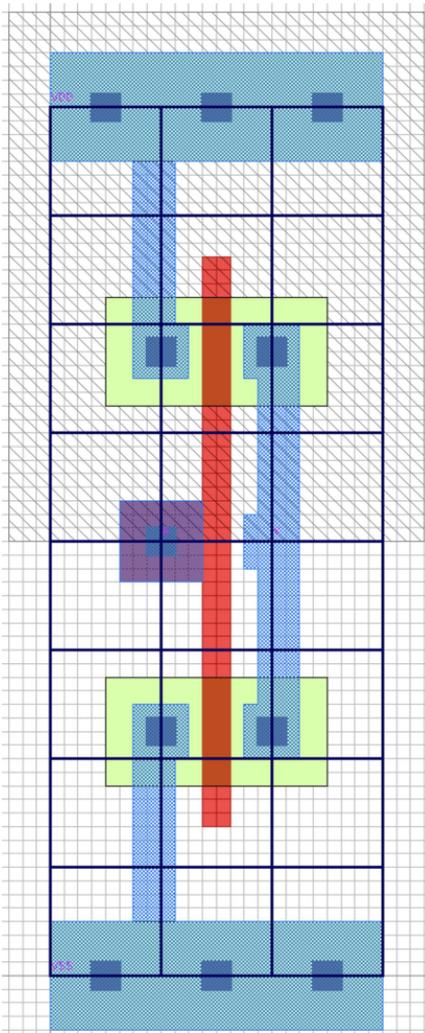
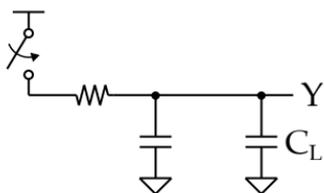
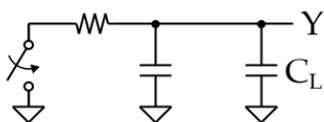
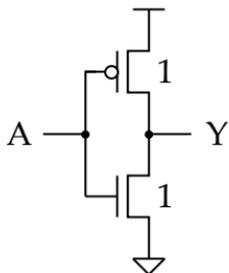
Cell Width

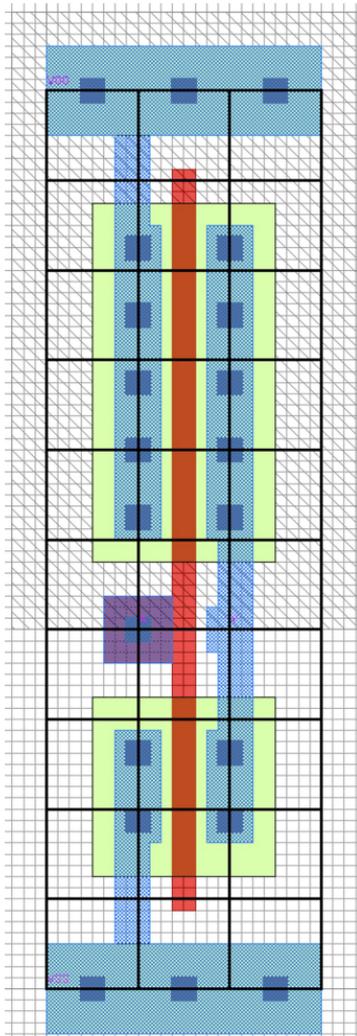
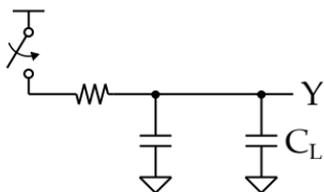
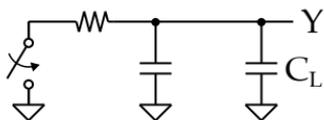
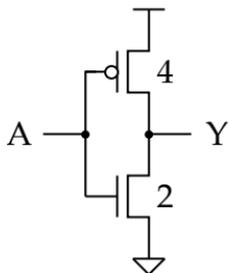
A Pin Location

Y Pin Location

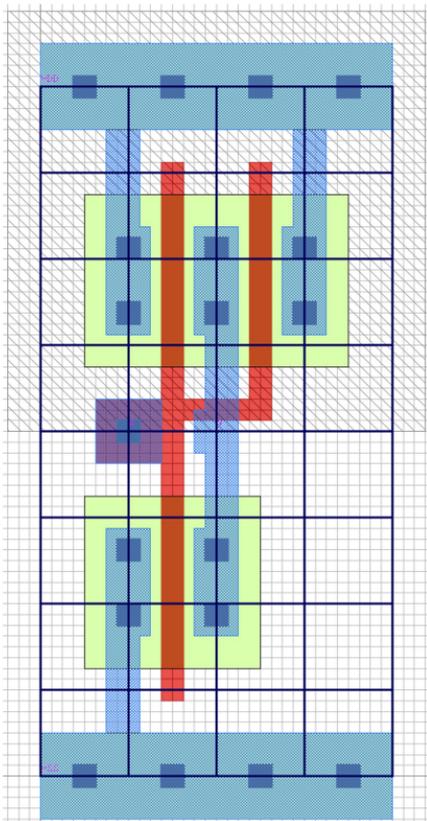
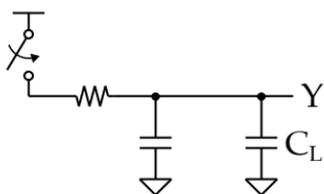
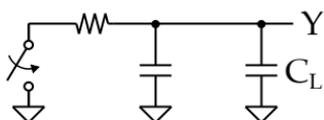
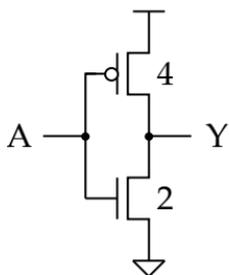
Aside: Abstract delay units

- We often want to analyze delay in “abstract delay units”
- Let τ be the propagation delay of an unloaded INVX1 standard cell
- $\tau = 3RC + RC_L = 3RC + R(0) = 3RC$

Aside: Inverter with non-equal rise and fall times

Aside: Inverter with $2\times$ drive strength

Aside: Inverter with $2\times$ drive strength with fingers



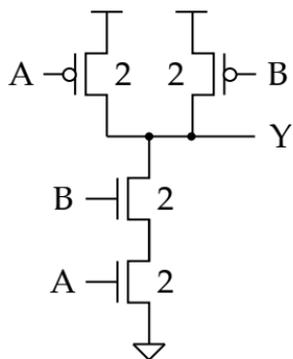
3.2. NAND2X1

Behavioral View

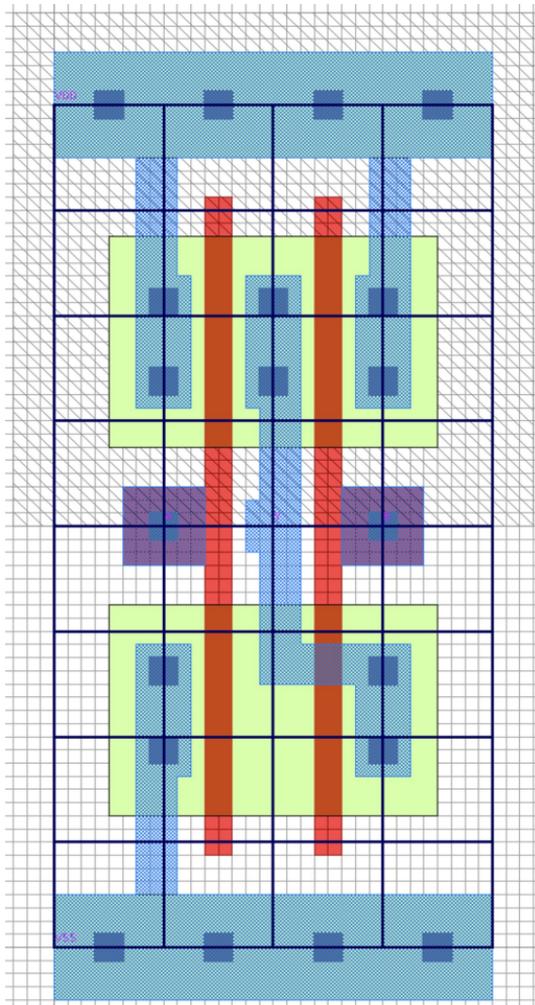
| A | B | Y |
|---|---|---|
| 0 | 0 | 1 |
| 0 | 1 | 1 |
| 1 | 0 | 1 |
| 1 | 1 | 0 |

$$Y = \overline{AB}$$

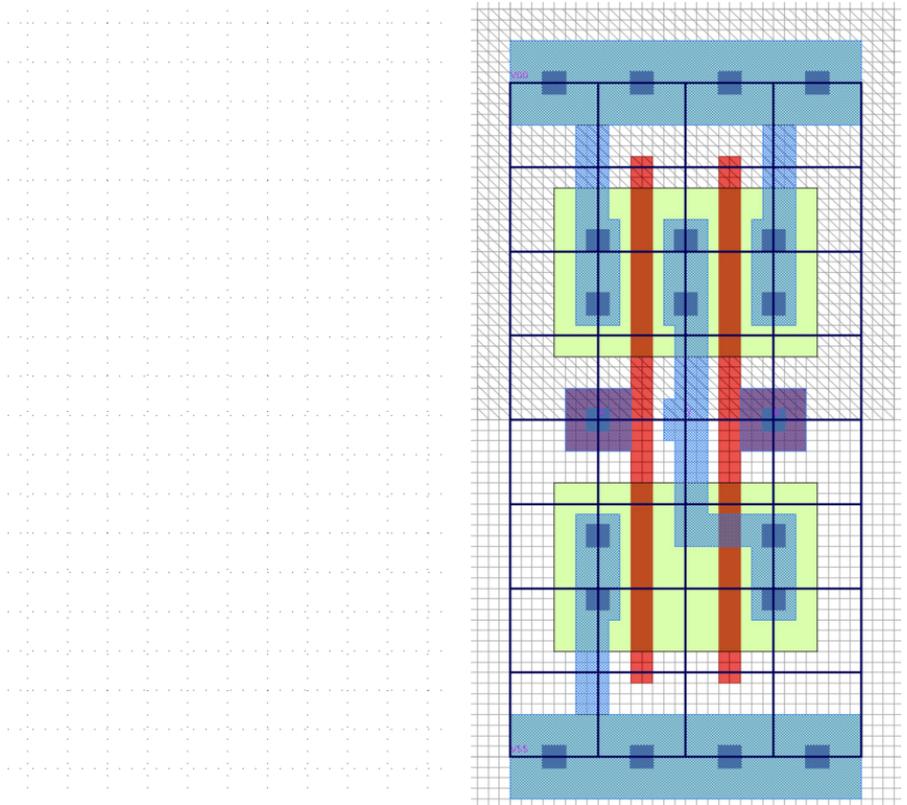
Schematic View



Layout View

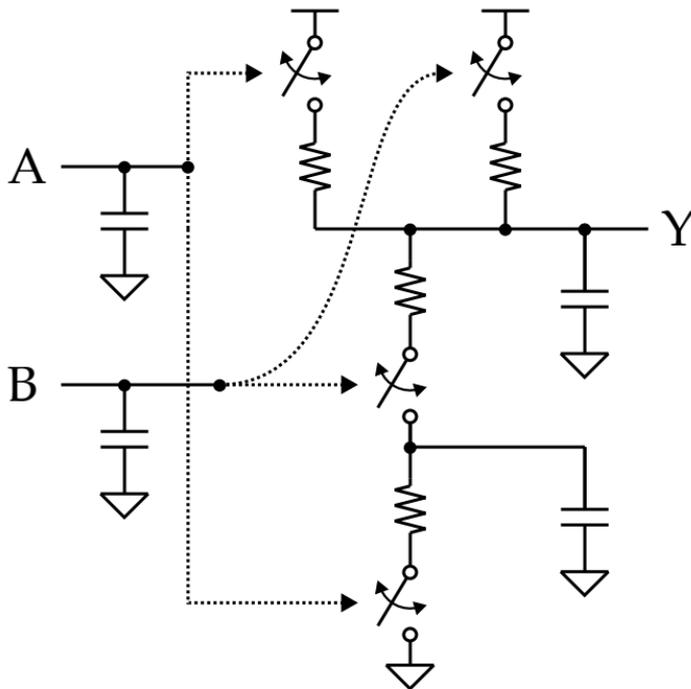


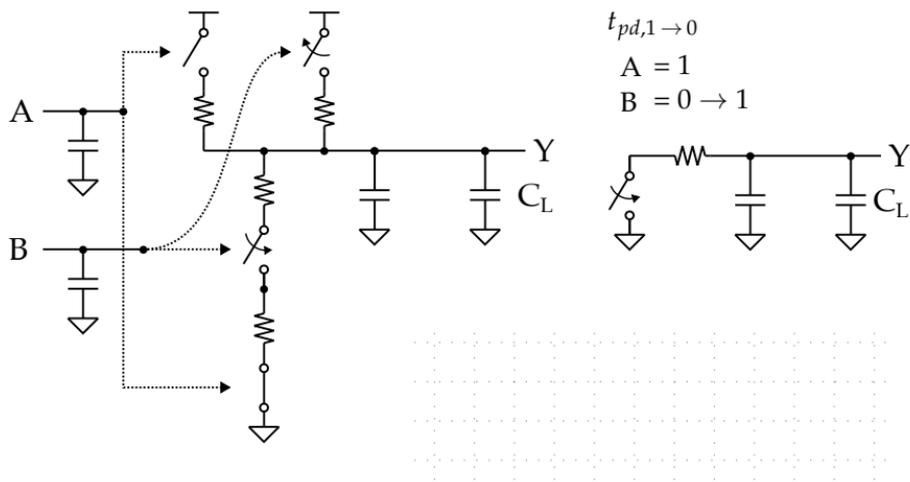
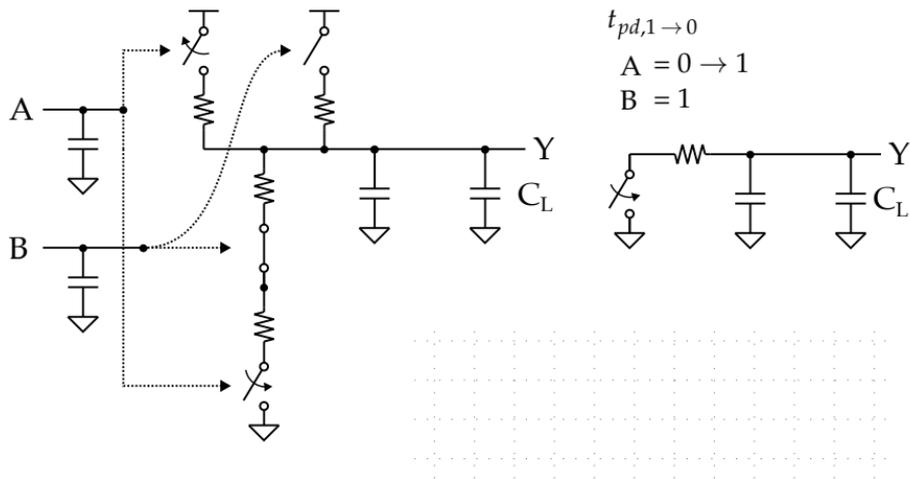
- Stick diagrams enable sketching a plan before detailed layout

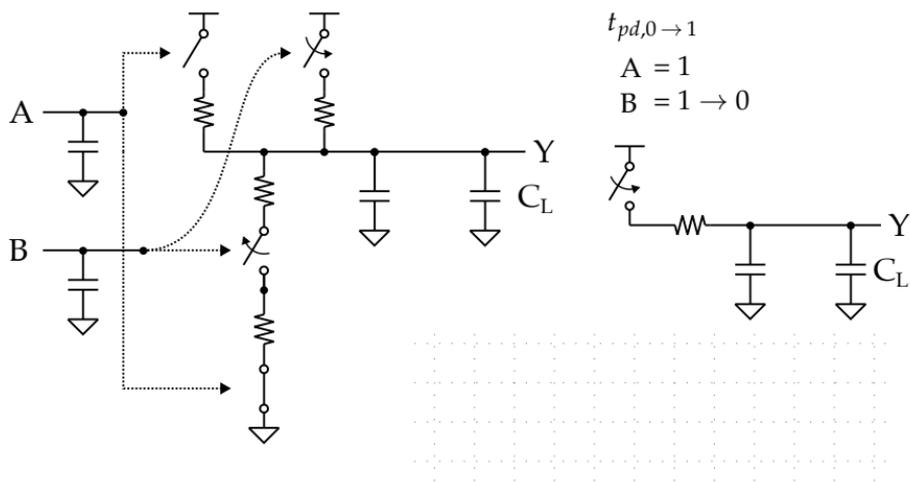
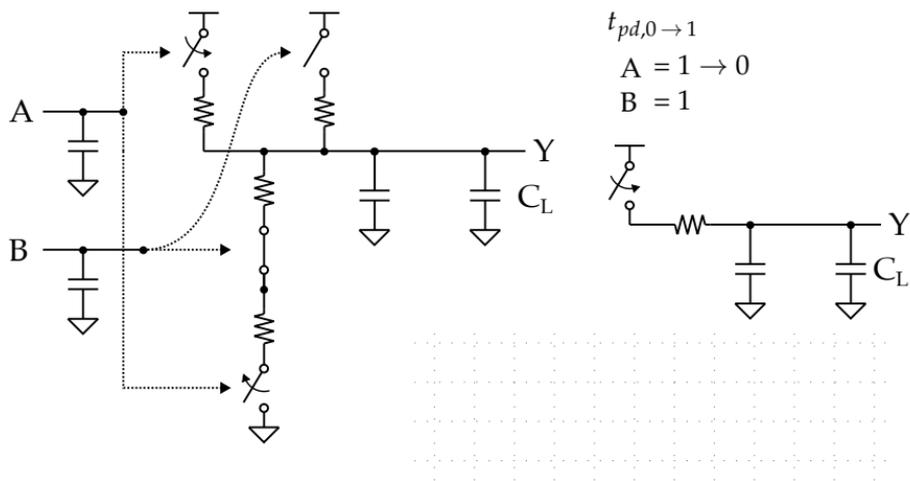


Extracted Schematic View

- Label the effective resistance and capacitance values to complete the extracted schematic model







Front-End View

Cell Area

A Input Cap

B Input Cap

Y Logic Function

Y Propagation Delay

Back-End View

Cell Height

Cell Width

A Pin Location

B Pin Location

Y Pin Location

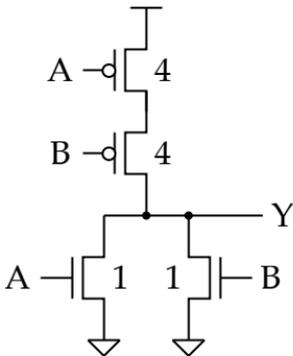
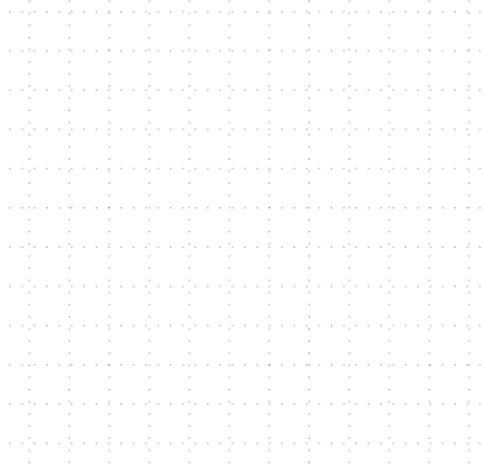
3.3. NOR2X1

Behavioral View

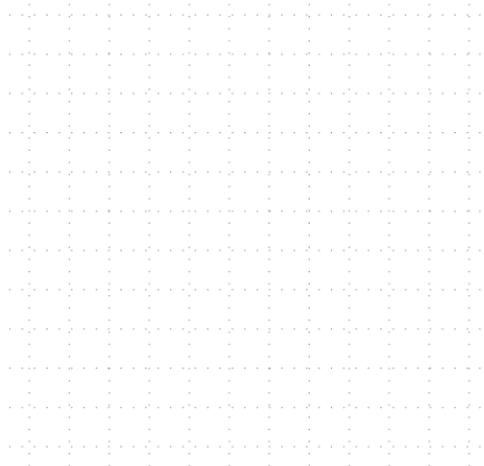
| A | B | Y |
|---|---|---|
| 0 | 0 | 1 |
| 0 | 1 | 0 |
| 1 | 0 | 0 |
| 1 | 1 | 0 |

$$Y = \overline{A + B}$$

Schematic View

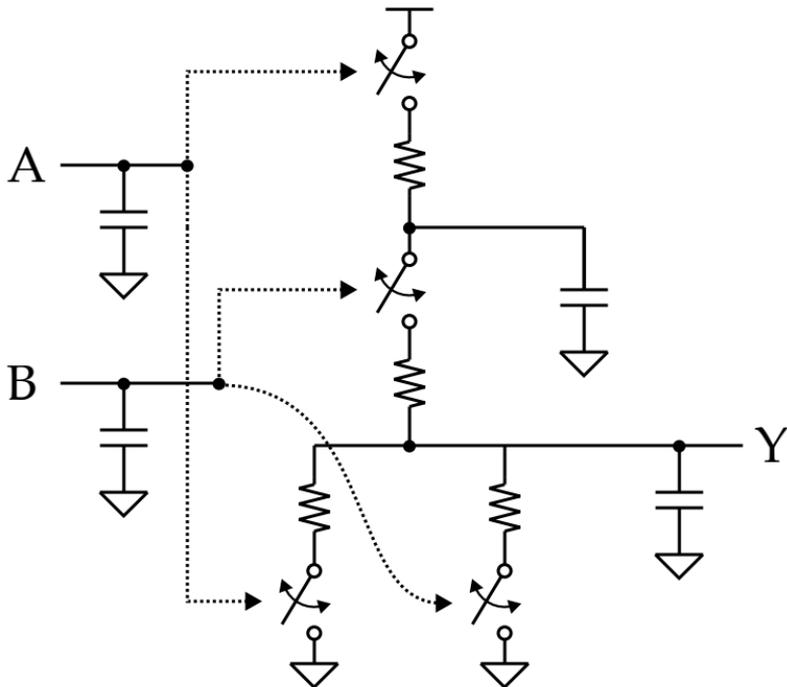
Layout View
(Stick Diagram without Fingers)

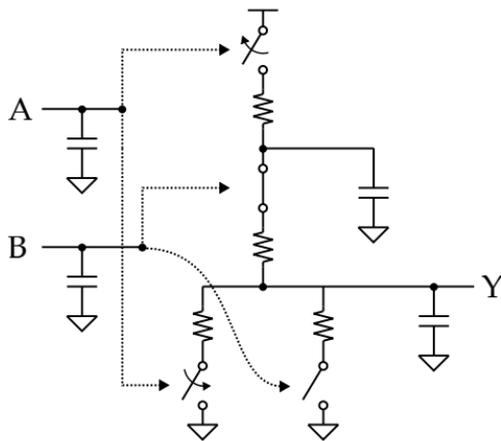
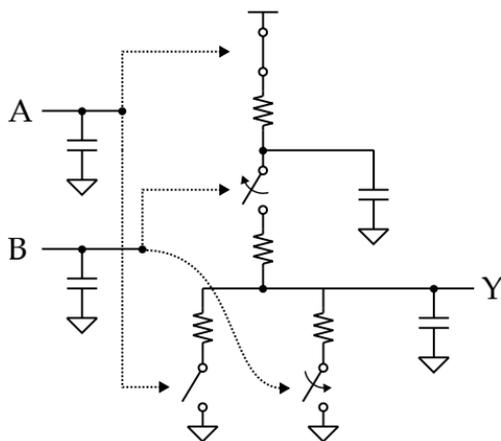
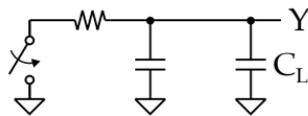
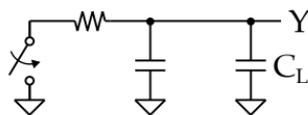
(Stick Diagram with Fingers)

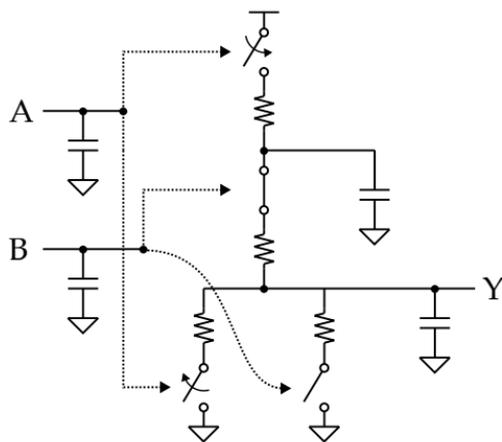
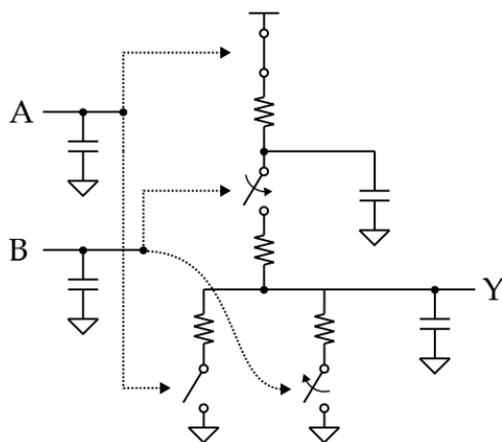
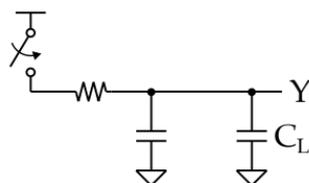
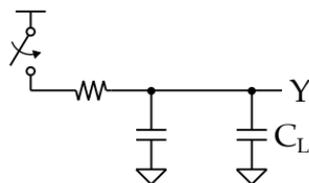


Extracted Schematic View

- Label the effective resistance and capacitance values to complete the extracted schematic model
 - Ignore internal capacitance
 - Assume layout-independent parasitic capacitance




 $t_{pd,1 \rightarrow 0}$
 $A = 0 \rightarrow 1$
 $B = 0$

 $t_{pd,1 \rightarrow 0}$
 $A = 0$
 $B = 0 \rightarrow 1$


 $t_{pd,0 \rightarrow 1}$ $A = 1 \rightarrow 0$ $B = 0$  $t_{pd,0 \rightarrow 1}$ $A = 0$ $B = 1 \rightarrow 0$ 

Front-End View

Cell Area

A Input Cap

B Input Cap

Y Logic Function

Y Propagation Delay

Back-End View

Cell Height

Cell Width

A Pin Location

B Pin Location

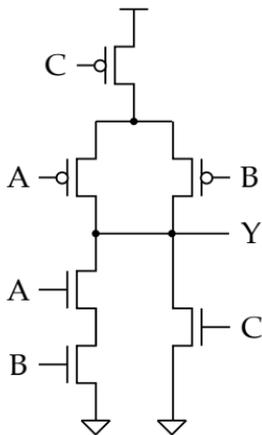
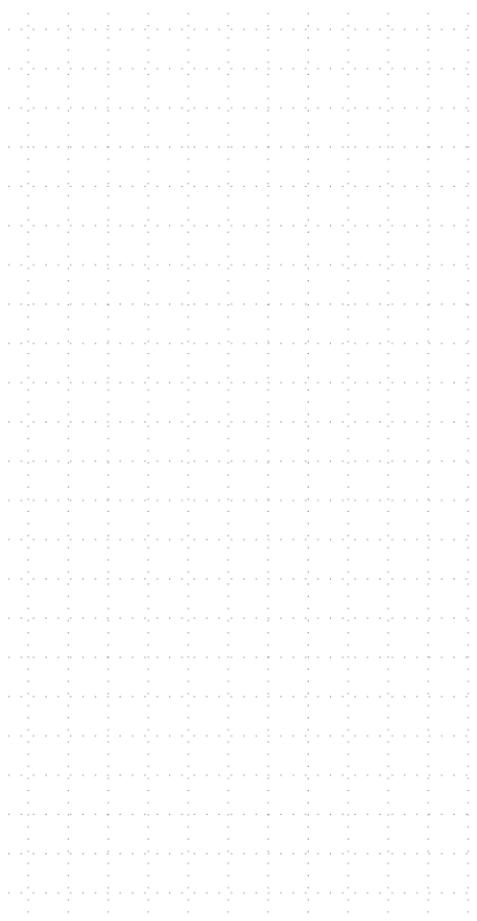
Y Pin Location

3.4. AOI21X1

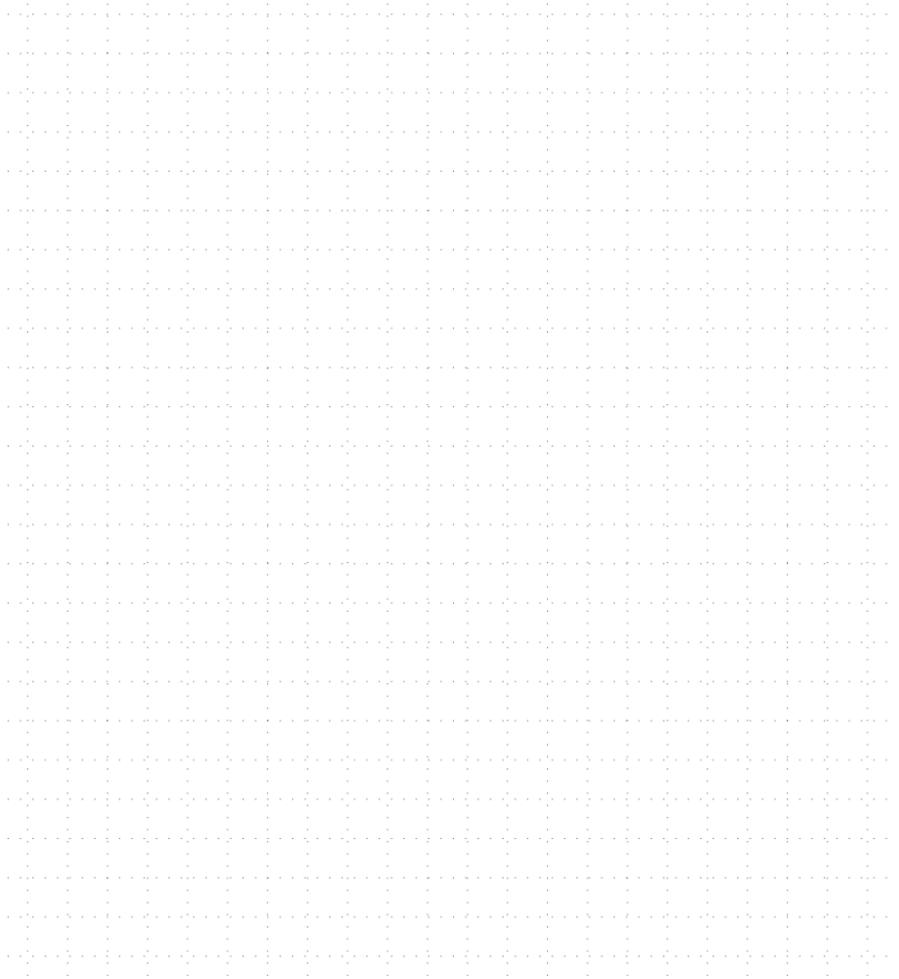
*(to do on your own)***Behavioral View**

| A | B | C | Y |
|---|---|---|---|
| 0 | 0 | 0 | 1 |
| 0 | 0 | 1 | 0 |
| 0 | 1 | 0 | 1 |
| 0 | 1 | 1 | 0 |
| 1 | 0 | 0 | 1 |
| 1 | 0 | 1 | 0 |
| 1 | 1 | 0 | 0 |
| 1 | 1 | 1 | 0 |

$$Y = \overline{AB + C}$$

Schematic View**Layout View**
(Stick Diagram)

Extracted Schematic View



Front-End View

Cell Area

A Input Cap

B Input Cap

C Input Cap

Y Logic Function

Y Propagation Delay

Back-End View

Cell Height

Cell Width

A Pin Location

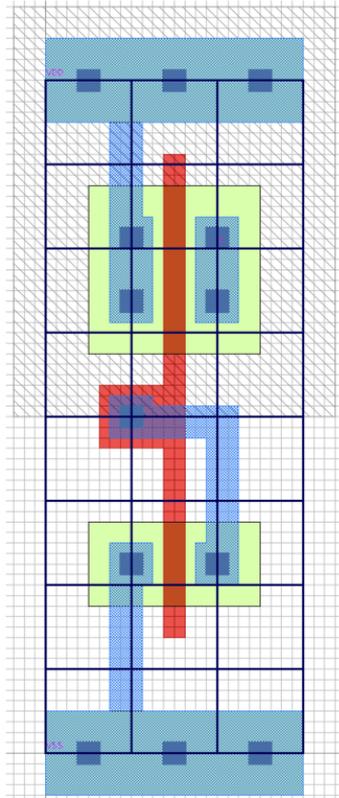
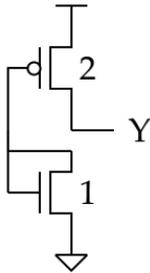
B Pin Location

C Pin Location

Y Pin Location

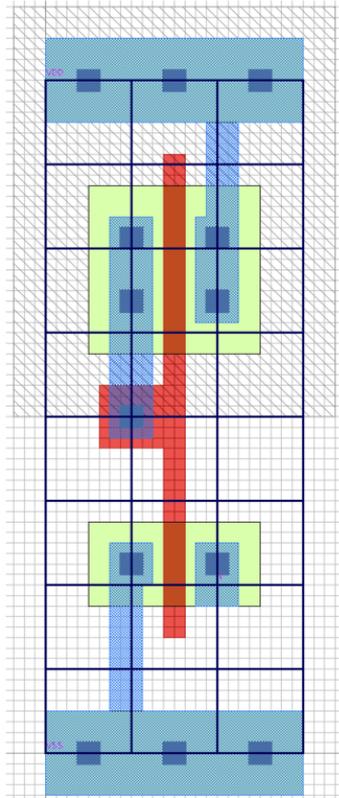
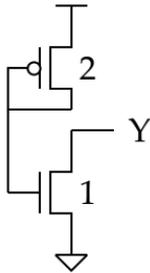
3.5. TIEHI

- Standard cell for connecting output to a constant logic one
- Do not directly connect a single net to the VDD supply rail
 - Power rails and signal nets can require different design rules
 - ESD on power rail can destroy fragile transistor gate
 - Power supply noise can cause signal to exceed noise margins



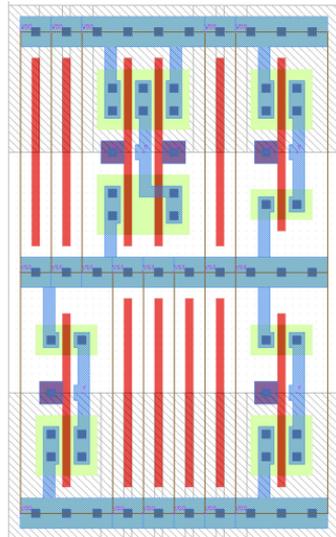
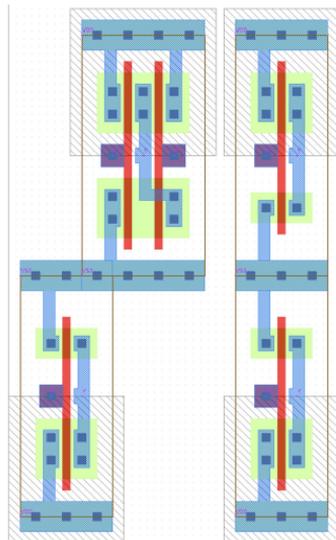
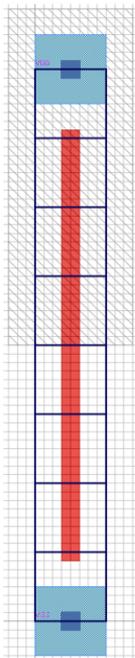
3.6. TIELO

- Standard cell for connecting output to a constant logic zero
- Do not directly connect a single net to the ground rail
 - Ground rails and signal nets can require different design rules
 - ESD on ground rail can destroy fragile transistor gate
 - Ground noise can cause signal to exceed noise margins

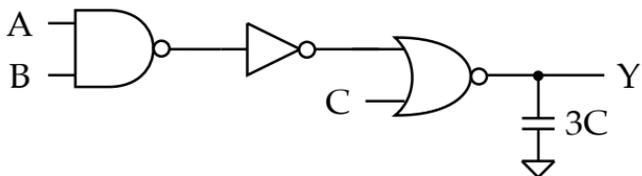
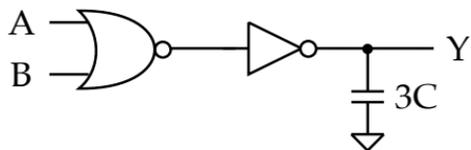


3.7. FILL

- Standard cell for filling in empty space along each row
- Needs to connect the power rail, ground rail, and n-well
- Need to include substrate and n-well contacts
- Needs polysilicon to satisfy polysilicon density design rules



4. Gate-Level Networks



5. TinyFlow: Standard-Cell Design Flow

5.1. Files

| | | |
|--------------------------|---------|-----------------|
| Behavioral View | Verilog | stdcells.v |
| Schematic View | SPICE | stdcells.sp |
| Layout View | GDS | stdcells.gds |
| Extracted Schematic View | SPICE | stdcells-rcx.sp |
| Front-End View | YAML | stdcells-fe.yml |
| Back-End View | YAML | stdcells-be.yml |

Behavioral View → Verilog

| | |
|---|---|
| A | Y |
| 0 | 1 |
| 1 | 0 |

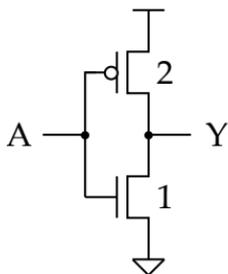
$$Y = \bar{A}$$

```

module INVX1
(
    input A,
    output Y
);
    assign Y = ~A;
endmodule

```

Schematic View → SPICE

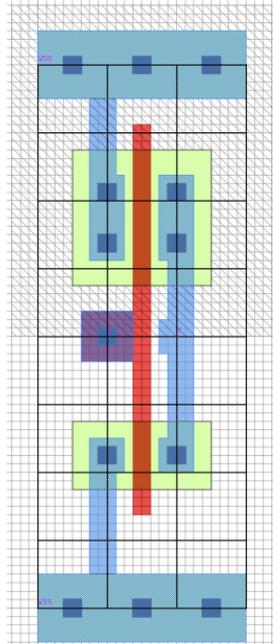
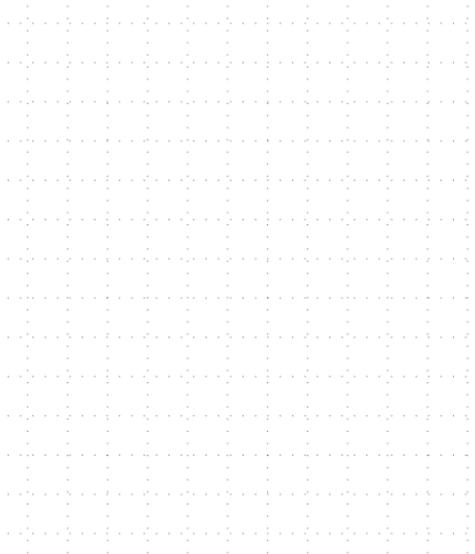


```

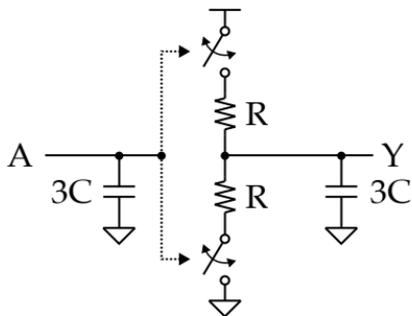
.SUBCKT INVX1 A Y VDD VSS
M_P Y A VDD VDD PMOS L=0.18U W=1.44U
M_N Y A VSS VSS NMOS L=0.18U W=0.72U
.ENDS INVX1

```

Layout View → GDS



Extracted Schematic View → SPICE



```
.SUBCKT INVX1 1 2 3 4

M$1 2 1 3 3 PMOS L=0.18U W=1.44U
    AS=0.9072P AD=0.9072P
    PS=4.14U PD=4.14U

M$2 2 1 4 4 NMOS L=0.18U W=0.72U
    AS=0.4536P AD=0.4536P
    PS=2.7U PD=2.7U

.ENDS INVX1
```

Front-End View → YAML

| | |
|--------------|--------------------|
| Cell Area | $1,536 \lambda^2$ |
| A Input Cap | $3C$ |
| Y Logic Func | $Y = \overline{A}$ |
| Y Prop Delay | $3RC + RC_L$ |

```
- name: INVX1
  area_cost: 1536 # lambda^2
  pins:
    - name: A
      type: input
      cgate: 3.6 # fF

    - name: Y
      type: output
      function: INV(A)

  parasitic_delay: 11.454 # ps
  load_delay_factor: 3.306 # ps/fF
```

Back-End View → YAML

| | |
|-------------|----------------------------|
| Cell Height | 64λ |
| Cell Width | 24λ |
| A Pin Loc | $(8 \lambda, 32 \lambda)$ |
| Y Pin Loc | $(16 \lambda, 32 \lambda)$ |

```
- name: INVX1
  size:
    width: 24
    height: 64
  pins:
    - name: A
      loc: (8,32)
    - name: Y
      loc: (16,32)
```

5.2. Tools

Icarus Verilog

TinyFlow-Ngspice

5.3. Flow

